

(19) World Intellectual Property
Organization
International Bureau



(43) International Publication Date
12 February 2004 (12.02.2004)

PCT

(10) International Publication Number
WO 2004/013693 A2

- (51) International Patent Classification⁷: **G03F**
- (21) International Application Number:
PCT/US2003/023948
- (22) International Filing Date: 31 July 2003 (31.07.2003)
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data:
10/210,785 1 August 2002 (01.08.2002) US
10/210,780 1 August 2002 (01.08.2002) US
10/210,894 1 August 2002 (01.08.2002) US
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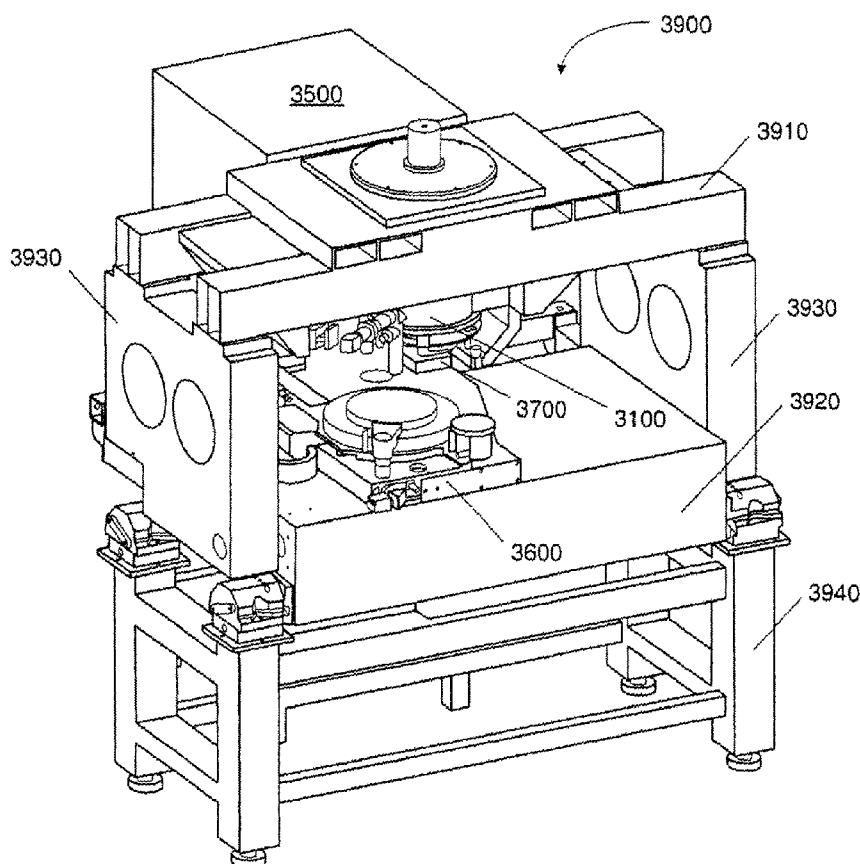
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(81) Designated States (national): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW,

[Continued on next page]

(54) Title: SCATTEROMETRY ALIGNMENT FOR IMPRINT LITHOGRAPHY



(57) Abstract: Described are methods for patterning a substrate by imprint lithography. Imprint lithography is a process in which a liquid is dispensed onto a substrate. A template is brought into contact with the liquid and the liquid is cured. The cured liquid includes an imprint of any patterns formed in the template. Alignment of the template with a previously formed layer on a substrate, in one embodiment, is accomplished by using scatterometry.



MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC,
SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA,
UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

SE, SI, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM,
GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

— *without international search report and to be republished
upon receipt of that report*

(84) Designated States (regional): ARIPO patent (GH, GM,
KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW),
Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM),
European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE,
ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO,

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ning of each regular issue of the PCT Gazette.*